(c) REMARKS

The claims are 28 and 29. Claim 28 has been to resolve an informality raised by the Examiner and also to clarify the intended invention.

Support for amended claim 28 is found at specification page 19, lines 12 to 17. The amendment is intended to show the embodiment in which at least one cylindrical substrate is set in each movable reactor. The shape of the cylindrical substrate set in one reactor is different from the shape of a cylindrical substrate set in the other reactors. Each reactor has an impedance. The impedance of one reactor is different from that of the other reactors because the shape of the cylindrical substrate set in one reactor is different from the shape of the cylindrical substrate set in one reactor is different from the shape of the cylindrical substrate set in the other reactors. Claim 28 has also been clarified to provide that one impedance matching circuit is provided to each of the plurality of different movable reactors. This amendment is intended to clarify that an impedance matching circuit is provided to each of the plurality of reactors.

Claims 28 and 29 were rejected for reasons of record. Prior to addressing the grounds of rejection, applicants wish to briefly discuss certain key features and advantages of the present claimed invention.

In the present invention, a shape of a cylindrical substrate set in a reactor is different from that of cylindrical substrate set in the other reactors. Accordingly, the impedance of the reactor is different from that of the other reactors. Of the reactors having different impedances from each other, one reactor is selected and is connected to one high frequency power source to process the reactor. Each reactor has a substrate having a different shape from that of the other reactors and further processing conditions (gas flow

rate) are different to each other. Therefore, impedances are different with regard to the respective reactors. Even though reactors having different impedances are connected under such conditions, a high frequency matching circuit (matching box) can be commonly used for each and microadjustments of impedance with the high frequency matching circuit (matching box) can be performed.

Turlot, et al. (US Patent No. 5,515,986) discloses a technique in which many work-pieces (substrates) are parallel processed (column 1, lines 16 to 18). It is, of course, assumed that the substrates to be set in each reactor are of substantially the same shape. Further, respective reactors (chambers) are processed under the same gas conditions (column 6, lines 53 to 61). Therefore, it is believed that all the reactors in Turlot, et al. have substantially the same impedance. In contrast, in the present claimed invention, as explained above, the shapes of the cylindrical substrates are different form each other and the impedances of the respective reactors are different from each other.

Turlot, et al. also discloses a technique in which, as shown in Fig. 5(c), when electric power is simultaneously supplied from one high frequency power source to a plurality of reactors, all the high frequency electric power to be introduced in respective reactors is equivalent (column 7, lines 6 to 9). In contrast, as explained above, the present invention does not use such a technique.

Turlot, et al., neither discloses nor suggests the feature that "each movable reactor having an impedance different from that of the other movable reactors due to a different shape of the cylindrical substrate set in each movable reactor".

Okamura (JP 11-319546) merely discloses that one impedance matching

circuit is provided to a plurality of reactors. In contrast, in the present invention, one

impedance matching circuit is provided to each reactor.

Therefore, none of the references, whether alone or combined, either

disclose or suggest the present invention nor render it unpatentable. The amendment

should be entered, the claims allowed and the case passed to issue.

Applicants' undersigned attorney may be reached in our New York office by

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Respectfully submitted,

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6